

AMENDMENTS

Please revise claims 1, 34, 37, 38, 41 and 42 as follows:

1. (Currently Amended) A positioning system, comprising:

a table having a surface to retain a workpiece;

a first flexible member that connects said table to a first movable base, the first flexible member being rigid to movement in ~~at least one~~ a first degree of freedom perpendicular to the surface, and flexible in other degrees of freedom;

a support structure that supports said first movable base; and

at least one magnetic actuator that ~~actuates~~ translates said first movable base in said ~~one~~ first degree of freedom.

2. (Original) The positioning system of claim 1, comprising at least one additional actuator to adjust the position of said table in at least a second degree of freedom.

3-4. (Previously Canceled)

5. (Original) The positioning system of claim 1, wherein said first movable base comprises a magnet, and said actuator comprises one or more coil assemblies.

6. (Original) The positioning system of claim 5, wherein a first said coil assembly includes a conduit therethrough, said first flexible member positioned in said conduit.

7. (Previously Canceled)

8. (Original) The positioning system of claim 1, said support structure comprising one or more bellows.

9. (Original) The positioning system of claim 1, said support structure comprising one or more springs.

10-33. (Previously Canceled)

34. (Currently Amended) The positioning system of claim 1, wherein the support structure permits movement of the first movable base in said ~~one~~ first degree of

freedom.

35. (Previously Added) The positioning system of claim 1, wherein the magnetic actuator is an EI core type actuator.

36. (Previously Added) The positioning system of claim 35, wherein the first movable base comprises an I component of the EI core type actuator.

37. (Currently Amended) An exposure apparatus, comprising:

a reticle stage having a surface to retain a reticle;

a first flexible member that connects the reticle stage to a first movable base, the first flexible member being rigid to movement in a first ~~at least one~~ degree of freedom perpendicular to the surface, and flexible in other degrees of freedom;

a support structure that supports the first movable base; and

at least one magnetic actuator that ~~actuates~~ translates the first movable base in the ~~one~~ first degree of freedom.

38. (Currently Amended) The positioning system of claim 37, wherein the support structure permits movement of the first movable base in said ~~one~~ first degree of freedom.

39. (Previously Added) The positioning system of claim 37, wherein the magnetic actuator is an EI core type actuator.

40. (Previously Added) The positioning system of claim 39, wherein the first movable base comprises an I component of the EI core type actuator.

41. (Currently Amended) An exposure apparatus, comprising:

a wafer stage having a surface to retain a wafer;

a first flexible member that connects the wafer stage to a first movable base, the first flexible member being rigid to movement in ~~at least one~~ a first degree of freedom perpendicular to the surface, and flexible in other degrees of freedom;

a support structure that supports the first movable base; and

at least one magnetic actuator that ~~actuates~~ translates the first movable base in the ~~one~~ first degree of freedom.

42. (Currently Amended) The positioning system of claim 41, wherein the support structure permits movement of the first movable base in said ~~one~~ first degree of freedom.

43. (Previously Added) The positioning system of claim 41, wherein the magnetic actuator is an EI core type actuator.

44. (Previously Added) The positioning system of claim 43, wherein the first movable base comprises an I component of the EI core type actuator.